FIG. 1

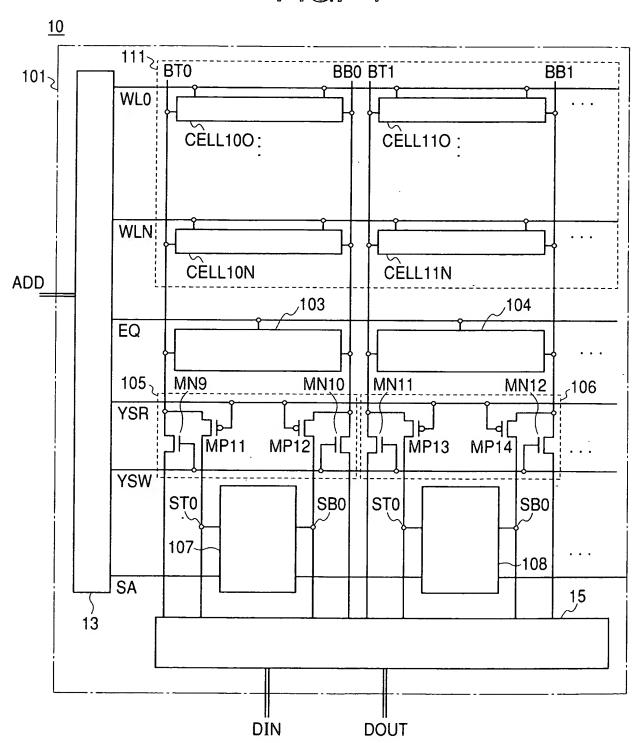


FIG. 2

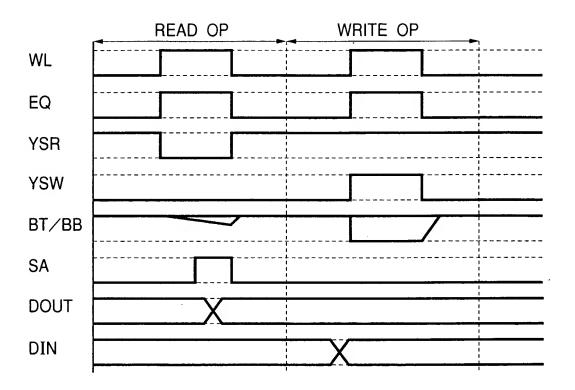


FIG. 3

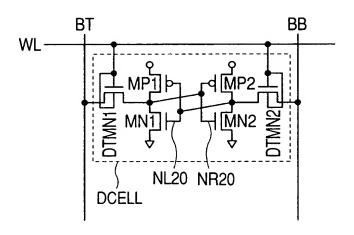


FIG. 4

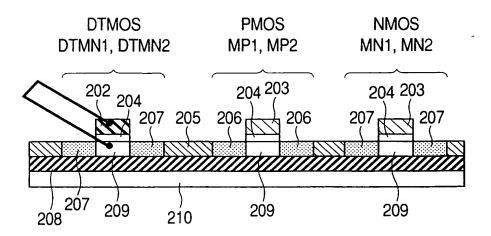


FIG. 5

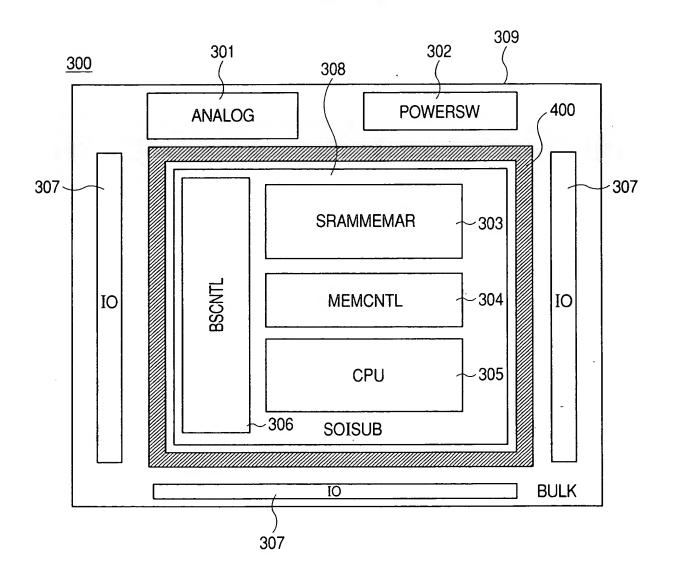
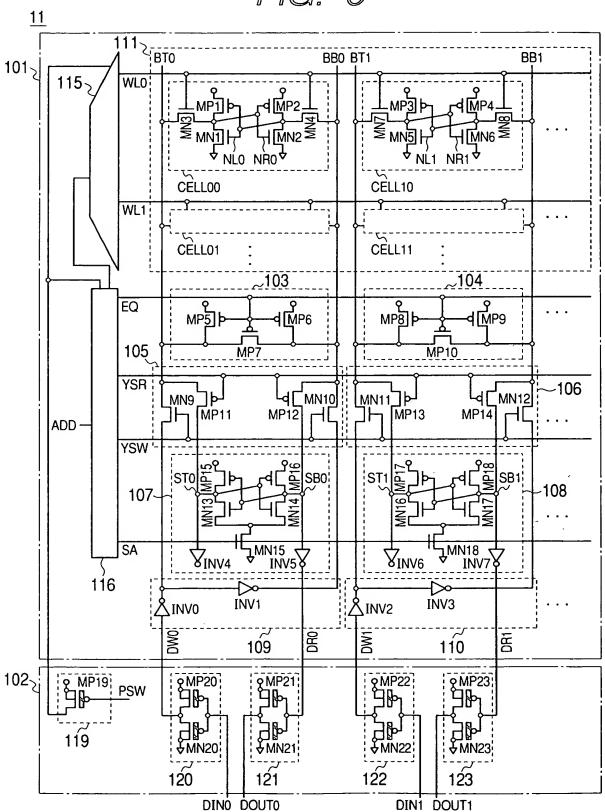


FIG. 6



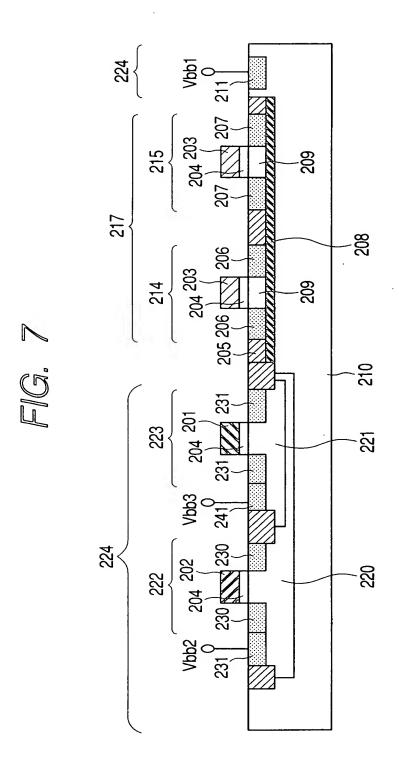


FIG. 8

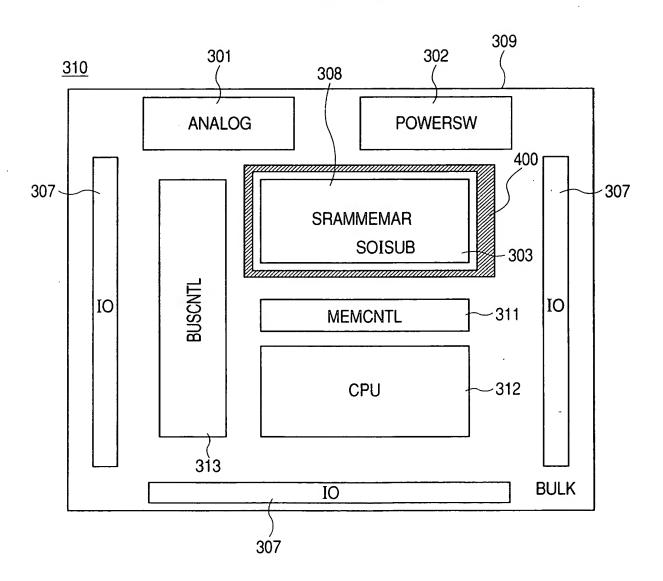


FIG. 9

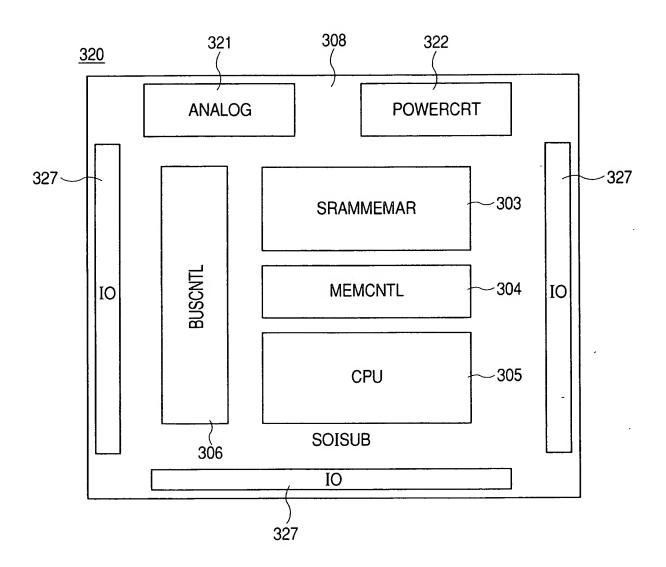
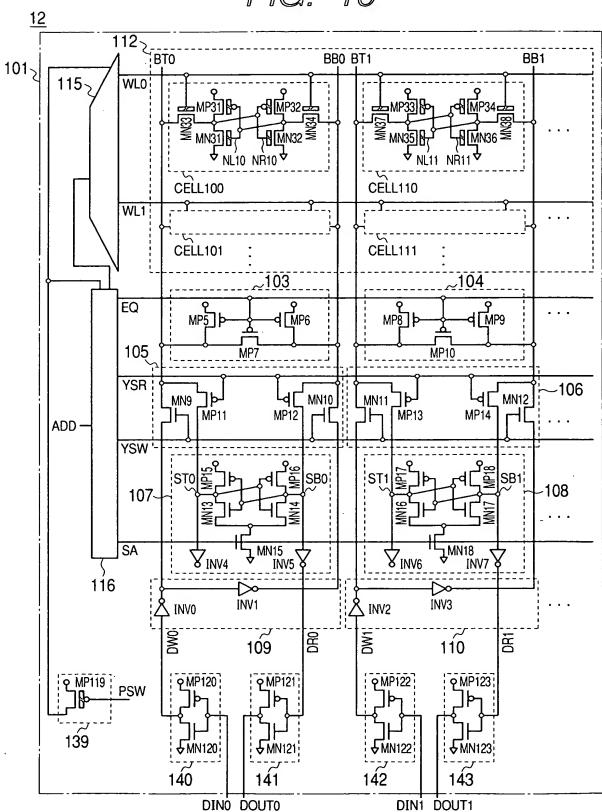
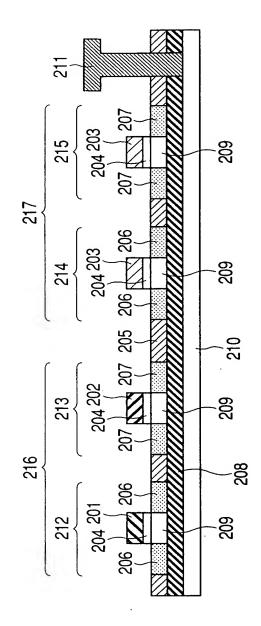


FIG. 10







7	1	
<b>(</b>	F	3
		7 7

	_	,				_		_			
	VT[V]	-0.3	0.3	-1.0	9.0		VT(V)	-0.8	8.0	-0.8	0.8
	SOIVBB	38	30	38	38		SOIVBB	×	×	×	×
STANDARD	GATEIMP	a.	Ь	Z	d.	LOWPOWER	GATEIMP	Z	۵.	N	Ъ
	GATEMAT	SiGe	SiGe	Poly-Si	Poly-Si		GATEMAT	Poly-Si	Poly-Si	Poly-Si	Poly-Si
	SUB	SOI	SOI	SOI	SOI		SUB	SOI	SOI	SOI	SOI
	VT[V]	-0.3	0.3	-0.3	0.3		VT[V]		9.0		9.0
	SOIVBB	0	0	0	0		SOIVBB	VERTICALMOS	3V	ALMOS	30
HIGHSPEED	GATEIMP	Ф	a.	ο.	Ъ	STANDARD	GATEIMP	VERTIC	Ь	VERTICALMOS	d
	GATEMAT	SiGe	SiGe	SiGe	SiGe		GATEMAT		Poly-Si		Poly-Si
	SUB	SOI	SOI	SOI	SOI		SUB	SOI	SOI	IOS	SOI
912	J and	PMISFET	NMISFET	PMISFET	NMISFET	gratos	ane	PMISFET	NMISFET	PMISFET	NMISFET
013103	TOC .	OI O	רטפוני	7400	OHAM		Ď	Ç	רטפור	71703	SHAM

GAIT	מוזיטוו			HIGHSPEED					STANDARD		
חים	HIBRIDSOB	SUB	GATEMAT	GATEIMP	SOIVBB	[V]LV	ans	GATEMAT	GATEIMP	SOIVBB	VT[V]
OI O	PMISFET	IOS	SiGe	d	0	-0.3	IOS	SiGe	d	3V	-0.3
2001	NMISFET	IOS	SiGe	d	0	0.3	IOS	SiGe	Ь	30	0.3
71700	PMISFET	IOS	SiGe	d	0	-0.3	IOS	Poly-Si	Z	30	-1.0
SHAM	NMISFET	SOI	SiGe	ď	0	0.3	IOS	Poly-Si	d.	30	9.0
IO/Analog/SW	/SW	BULK	,	1		ANY	BULK	-	1	-	ANY
מאוו	מווסטונ			STANDARD					LOWPOWER		
בים	סטפטואפזר	SUB	GATEMAT	GATEIMP	SOIVBB	[V]LV	ans	GATEMAT	GATEIMP	SOIVBB	VT[V]
0	PMISFET	BULK	,	_	1	ANY	BULK	*	1	-	ANY
רטפוני	NMISFET	BULK	1	1	1	ANY	YINB	-	1	,	ANY
7140	PMISFET	SOI	,	VERTIC	VERTICALMOS		IOS	Poly-Si	Ν	×	-0.8
SHAM	NMISFET	IOS	SiGe	Ь	NONE	0.5	IOS	Poly-Si	Ь	×	0.8
IO/Analog/SW	/SW	BULK	1	•		ANY	BULK		1	ŧ	ANY

## FIG. 13

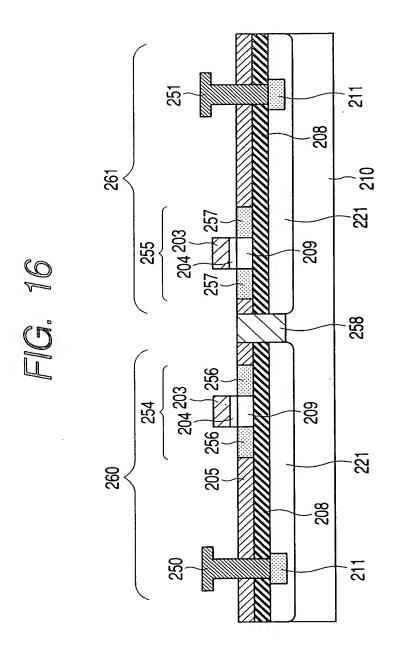
		HIGH SPEED	STANDARD	LOW POWER
		300MHz~	100MHz~300MHz	~100MHz
		Vdd<1.0V	Vdd≒1.0V	Vdd>1.0V
Logic	PMOSVT	-0.3V~-0.1V	-0.4V~-0.2V	-0.9V <b>~</b> -0.7V
	NMOSVT	0.1V~0.3V	0.2V~0.4V	0.7V~0.9V
SRAM	PMOSVT	-0.5V~-0.3V	-1.0V~-0.8V	-0.9V~-0.7V
	NMOSVT	0.2V~0.4V	0.4V~0.6V	0.7V~0.9V

FIG. 14

GATE MAT	Poly-Si		SiGe	
GATE IMP	Р	N	Р	N
PMOS Vto	+0.2V	-0.8V	-0.1V	-0.8V
NMOS Vto	+0.8V	-0.2V	0.5V	-0.2V

## FIG. 15

	ELE	BULK	FD-SOI
Vbbb	LVthMOS + VBBBCRT	EFFECT IS LOW UNDER 100nm	EFFECT EVEN UNDER 100nm
Vbbf	HVthMOS + VBBFCRT	EFFECT IS LOW AT HIGH TEMPERATURE LEAK CURRENT IS LARGE	HIGH TEMPERATURE OPERATION AVAILABLE, SMALL LEAK CURRENT, ON CURRENT LARGE
Vbbact	VthMOS + MNTCRT + VLTCRT	WITH ABOVE REASONS, CORRECTIONS FOR VTH DISPERSION IS NOT EFFECTIVE	EFFECTIVE UNDER 100nm & HIGH TEMPERATURE



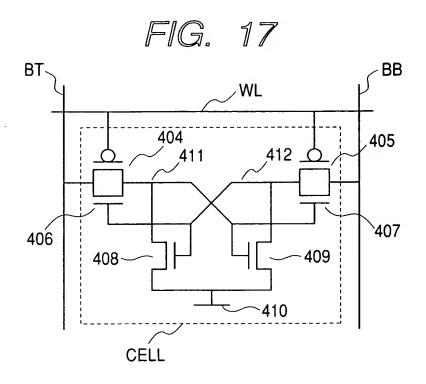


FIG. 18

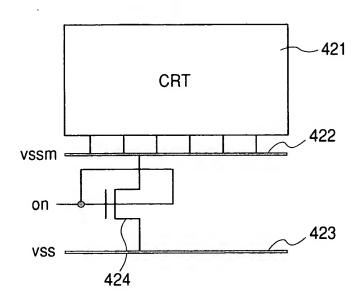


FIG. 19

